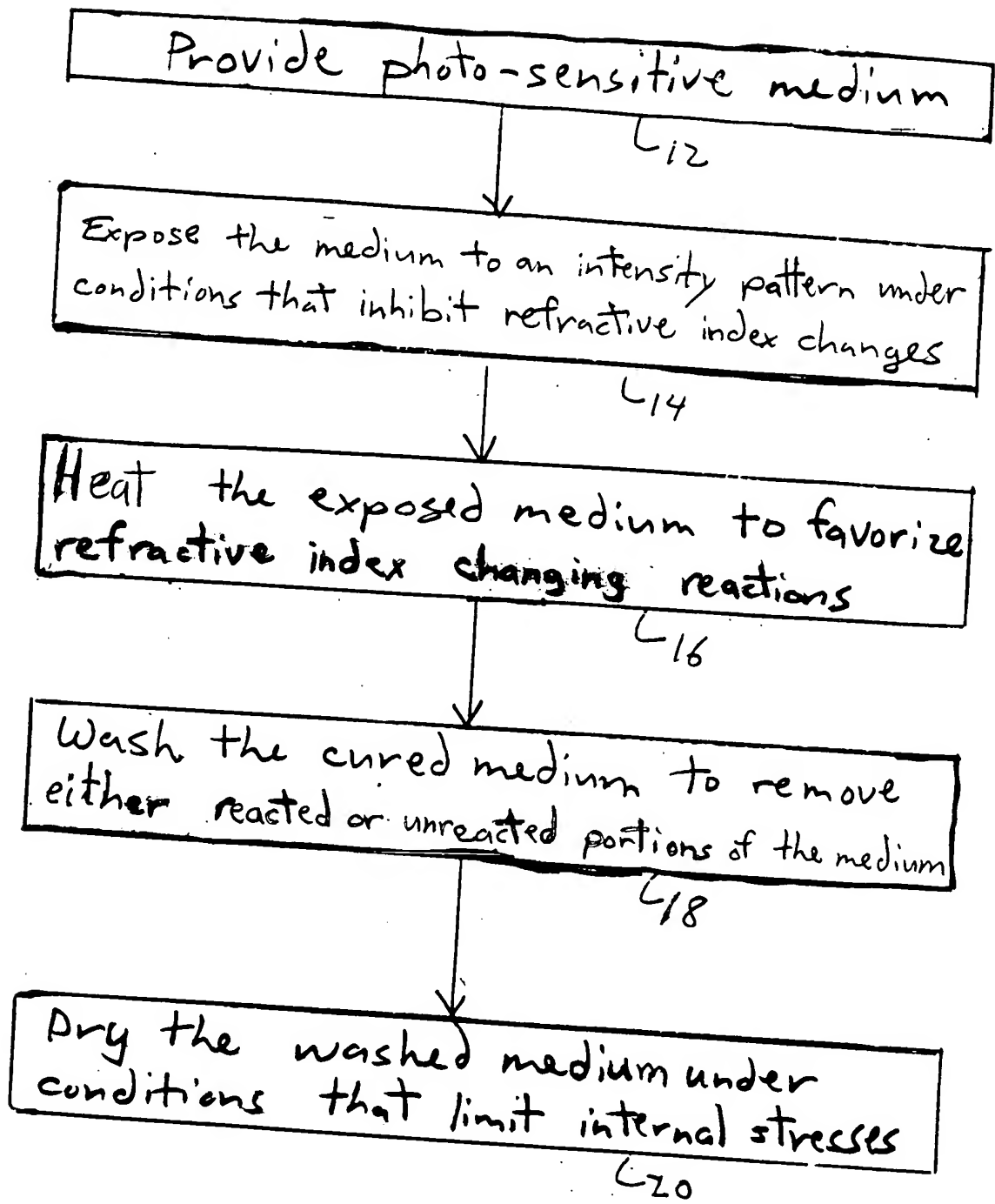


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FIG. 1

FIG. 2B

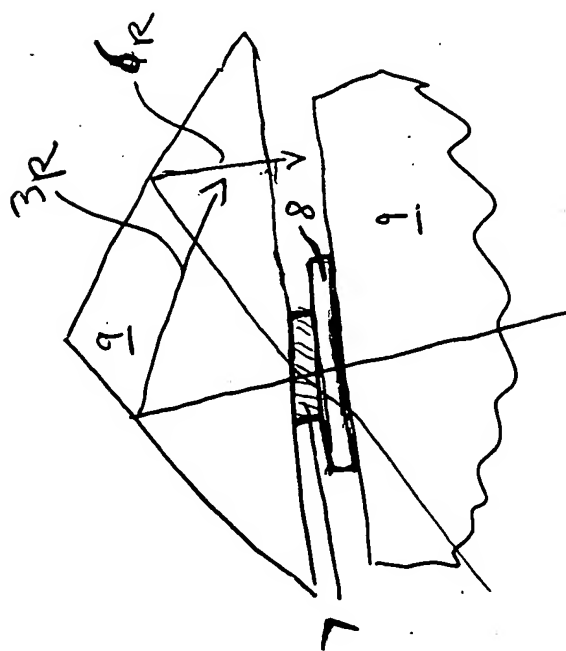


FIG. 2A

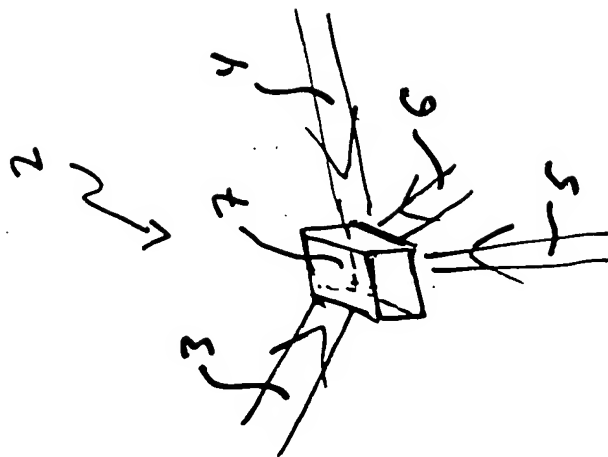


FIG. 3

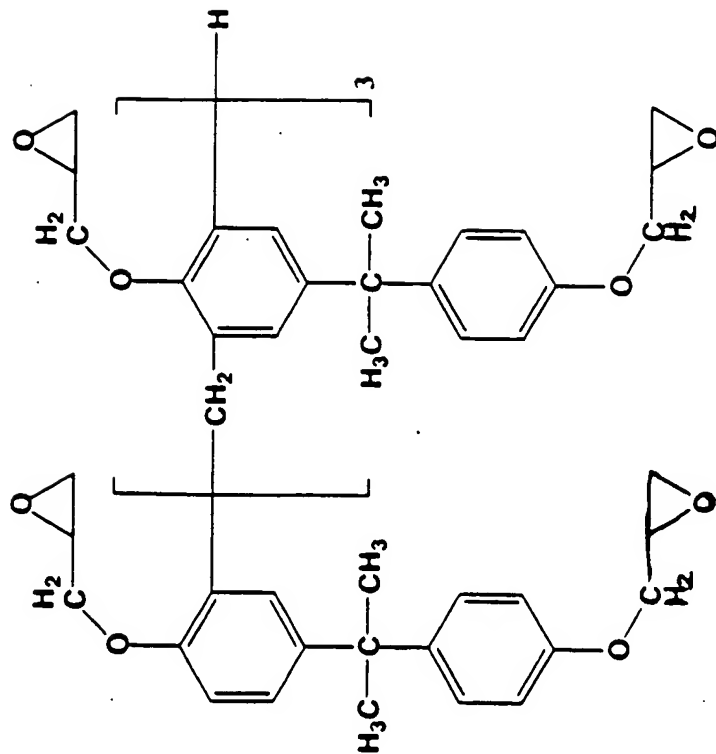


FIG. 4A

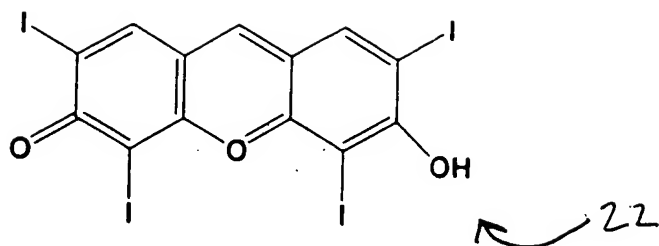


FIG. 4B

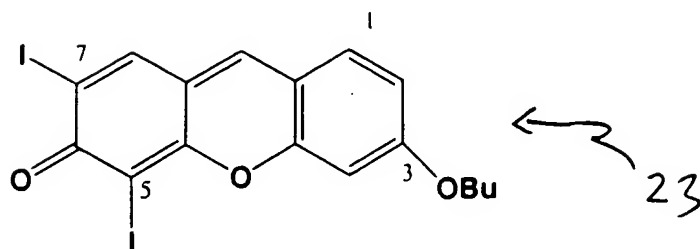


FIG. 4C

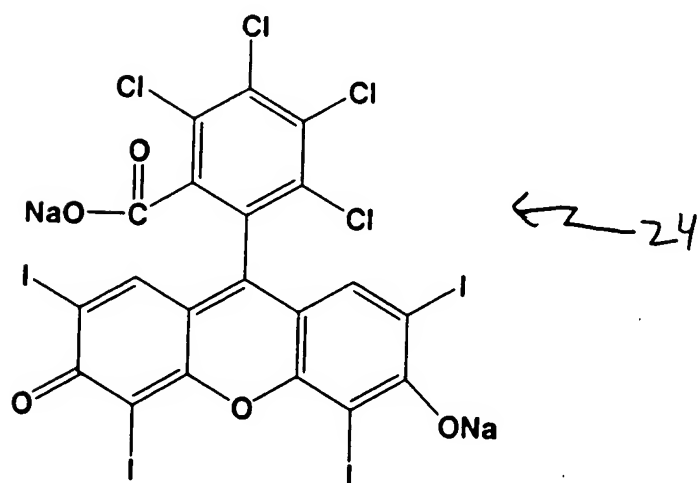


FIG. 5A

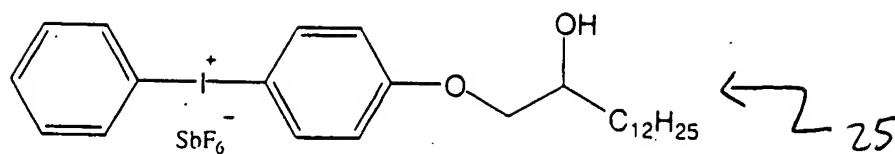


FIG. 5B

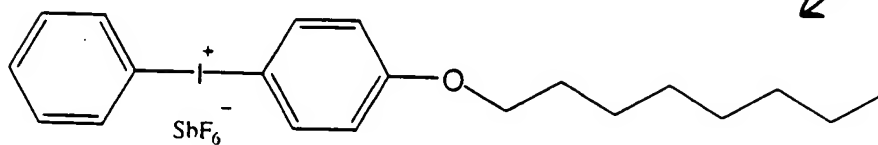
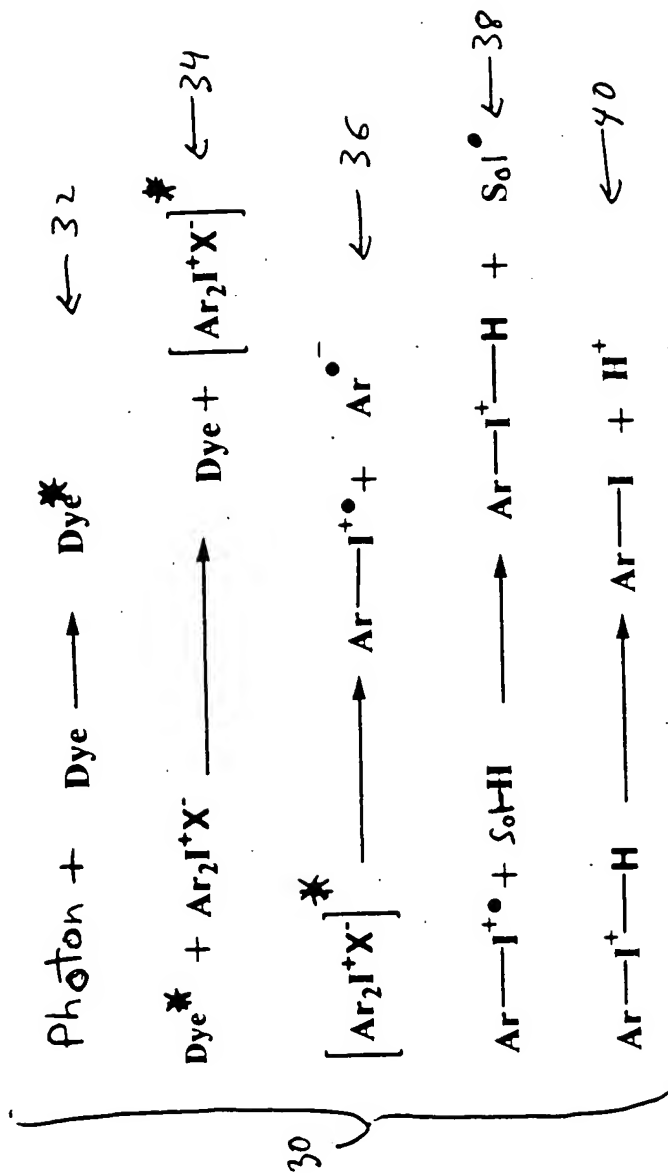
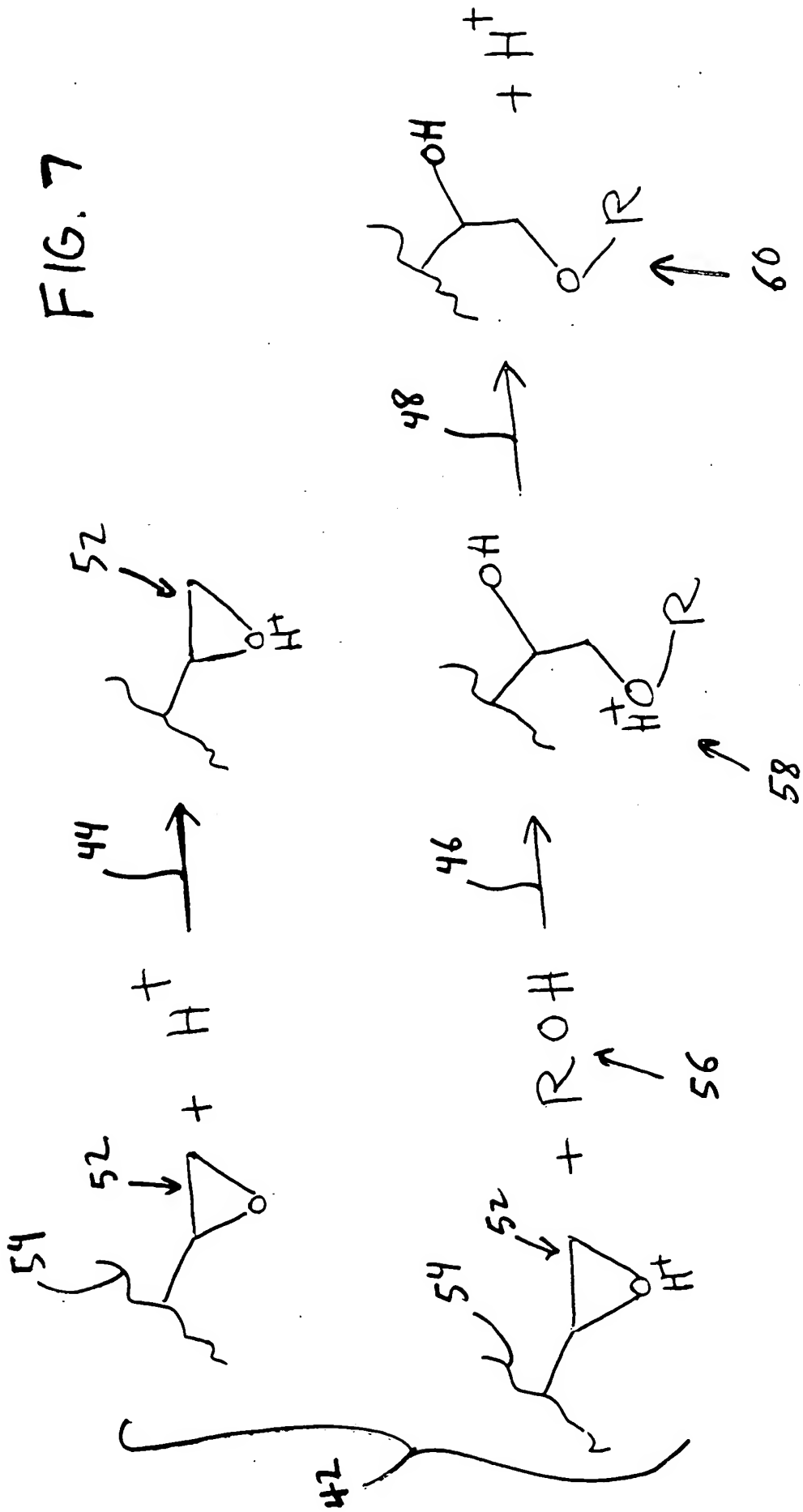


FIG. 6





Provide photo-sensitive medium

C12

Expose the medium to an intensity-pattern
under conditions that inhibit refractive index changes

C14

Sequentially expose a selected set
of points and/or lines with a focal
region of a converging light beam

C72

Heat the exposed medium to
favorize polymerization of oligomers
therein

C16

Wash the cured medium to remove
unpolymerized oligomers

C18

Dry the washed medium under
conditions that limit internal stresses

C20

70

FIG. 9

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Form a 3D polymer crystalline template

82

Fill holes in the template with a high refractive index filler material

84

Burn or etch away the polymer crystalline template from the block

86

80

FIG. 9

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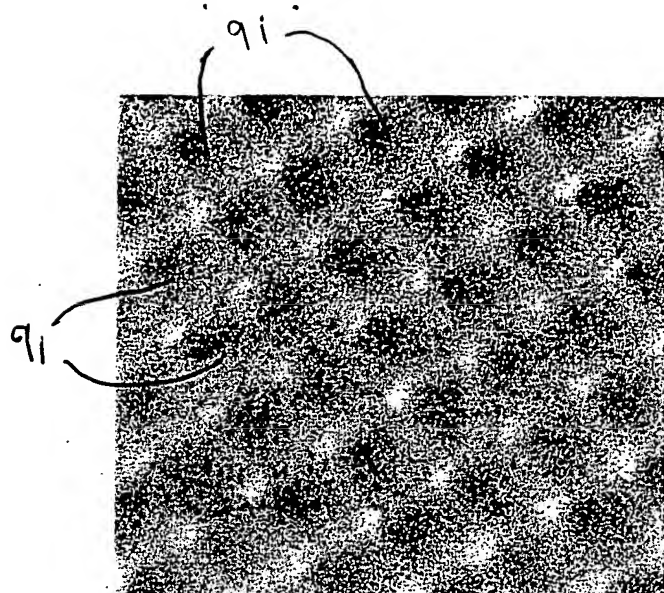


FIG. 10

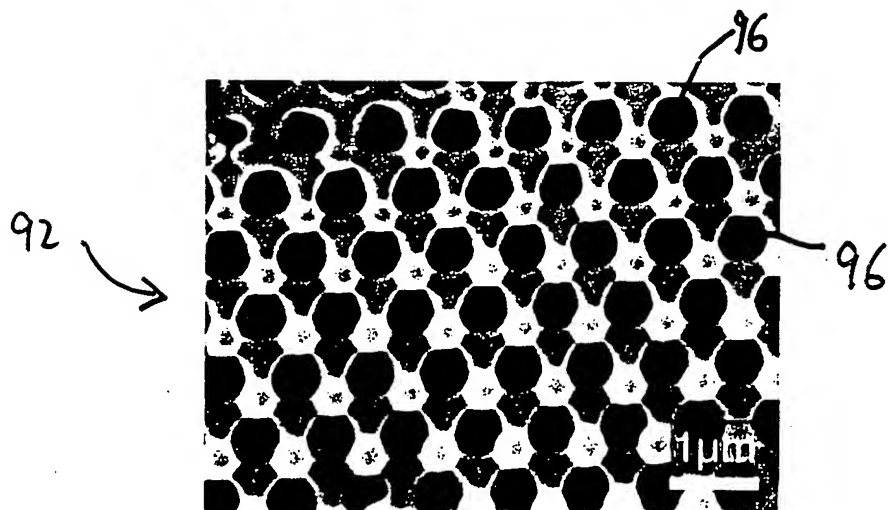


FIG. 11A

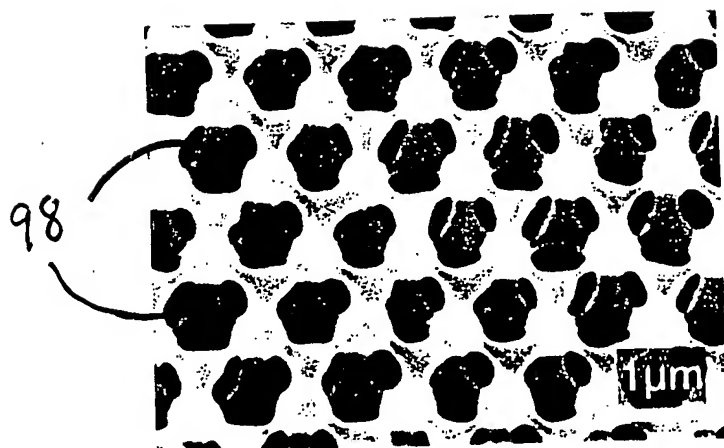


FIG. 11B